

=> s polybenzazole# and light-resist?

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      113 POLYBENZAZOLE#
      788669 LIGHT
      945548 RESIST?
      3284 LIGHT-RESIST?
          (LIGHT(W) RESIST?)
L1      1 POLYBENZAZOLE# AND LIGHT-RESIST?

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L1      ANSWER 1 OF 1  USPATFULL
AN      1999:155347  USPATFULL
TI      Polybenzazole fiber and method for production thereof
IN      Teramoto, Yoshihiko, Ohtsu, Japan
          Kitagawa, Tooru, Ohtsu, Japan
          Tanaka, Yoshikazu, Ohtsu, Japan
          Ishitobi, Michio, Ohtsu, Japan
PA      Toyo Boseki Kabushiki Kaisha, Japan (non-U.S. corporation)
PI      US 5993963  19991130
AI      US 1997-940780  19970930 (8)
PRAI    JP 1996-260895      19961001
DT      Utility
LN.CNT  564
INCL     INCLM: 428/364.000
          INCLS: 428/394.000
NCL      NCLM: 428/364.000
          NCLS: 428/394.000
IC      [6]
          ICM: D02G003-00
EXF      428/357; 428/364; 428/394; 428/359

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=> s polybenzazole# and regular reflectance#

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      113 POLYBENZAZOLE#
      143337 REGULAR
      24067 REFLECTANCE#
          23 REGULAR REFLECTANCE#
              (REGULAR(W) REFLECTANCE#)
L2      0 POLYBENZAZOLE# AND REGULAR REFLECTANCE#

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=> s polybenzazole# and reflectance#

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      113 POLYBENZAZOLE#
      24067 REFLECTANCE#
L3      2 POLYBENZAZOLE# AND REFLECTANCE#

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=> s polybenzazole# and wavelength#

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      113 POLYBENZAZOLE#
      151152 WAVELENGTH#
L4      8 POLYBENZAZOLE# AND WAVELENGTH#

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=> d 13 1-2

L3 ANSWER 1 OF 2 USPATFULL
AN 1999:33748 USPATFULL
TI Photocurable formulation containing a partially polymerized
divinylsiloxane linked bisbenzocyclobutene resin
IN Foster, Pamela S., Midland, MI, United States
Ecker, Ernest L., Midland, MI, United States
Rutter, Jr., Edward W., Midland, MI, United States
Moyer, Eric S., Midland, MI, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5882836 19990316
AI US 1995-465664 19950605 (8)
RLI Division of Ser. No. US 1994-224203, filed on 14 Apr 1994 which is a
continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993
DT Utility
LN.CNT 1491
INCL INCLM: 430/194.000
INCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000
NCL NCLM: 430/194.000
NCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000
IC [6]
ICM: G03C001-52
ICS: C08C002-48
EXF 430/286; 430/287; 430/286.1; 430/287.1; 430/194; 522/99; 522/65
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 2 OF 2 USPATFULL
AN 1998:162564 USPATFULL
TI Partially polymerized divinylsiloxane linked bisbenzocyclobutene resins
and methods for making said resins
IN Foster, Pamela S., Midland, MI, United States
Ecker, Ernest L., Midland, MI, United States
Rutter, Jr., Edward W., Midland, MI, United States
Moyer, Eric S., Midland, MI, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5854302 19981229
AI US 1994-224203 19940414 (8)
RLI Continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993,
now abandoned
DT Utility
LN.CNT 1506
INCL INCLM: 522/172.000
INCLS: 526/281.000; 528/032.000; 556/453.000
NCL NCLM: 522/172.000
NCLS: 526/281.000; 528/032.000; 556/453.000
IC [6]
ICM: C08F002-46
ICS: C08F010-08; C08G077-20
EXF 522/172; 526/281; 528/32; 556/453; 428/391
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> d 14 1-8

L4 ANSWER 1 OF 8 USPATFULL
AN 2000:84002 USPATFULL
TI Photodefineable cyclobutarene compositions
IN Oaks, Frank L., San Carlos, CA, United States
Moyer, Eric S., Midland, MI, United States

Rutter, Jr., Edward W., Midland, MI, United States
Harris, Robert F., Midland, MI, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 6083661 20000704
AI US 1994-290197 19940815 (8)
RLI Continuation-in-part of Ser. No. US 1991-805395, filed on 10 Dec 1991,
now abandoned
DT Utility
LN.CNT 2011
INCL INCLM: 430/286.100
INCLS: 430/194.000; 430/287.100; 522/065.000; 522/099.000
NCL NCLM: 430/286.100
NCLS: 430/194.000; 430/287.100; 522/065.000; 522/099.000
IC [7]
ICM: G03C001-13
EXF 430/286; 430/287; 430/194; 522/160; 428/195
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 2 OF 8 USPATFULL
AN 2000:34296 USPATFULL
TI **Polybenzazole** fiber having high tensile modulus and process of
manufacture thereof
IN Kitagawa, Tooru, Ohtsu, Japan
Ishitobi, Michio, Ohtsu, Japan
PA Toyo Boseki Kabushiki Kaisha, Osaka-fu, Japan (non-U.S. corporation)
PI US 6040050 20000321
AI US 1998-97997 19980616 (9)
PRAI JP 1997-161554 19970618
JP 1997-280789 19971014
DT Utility
LN.CNT 870
INCL INCLM: 428/364.000
INCLS: 428/394.000
NCL NCLM: 428/364.000
NCLS: 428/394.000
IC [7]
ICM: B02G003-00
EXF 428/364; 428/394; 428/395; 264/205

L4 ANSWER 3 OF 8 USPATFULL
AN 1999:33748 USPATFULL
TI Photocurable formulation containing a partially polymerized
divinylsiloxane linked bisbenzocyclobutene resin
IN Foster, Pamela S., Midland, MI, United States
Ecker, Ernest L., Midland, MI, United States
Rutter, Jr., Edward W., Midland, MI, United States
Moyer, Eric S., Midland, MI, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5882836 19990316
AI US 1995-465664 19950605 (8)
RLI Division of Ser. No. US 1994-224203, filed on 14 Apr 1994 which is a
continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993
DT Utility
LN.CNT 1491
INCL INCLM: 430/194.000
INCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000
NCL NCLM: 430/194.000
NCLS: 430/286.100; 430/287.100; 522/065.000; 522/099.000
IC [6]
ICM: G03C001-52
ICS: C08C002-48
EXF 430/286; 430/287; 430/286.1; 430/287.1; 430/194; 522/99; 522/65
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 4 OF 8 USPATFULL
 AN 1998:162564 USPATFULL
 TI Partially polymerized divinylsiloxane linked bisbenzocyclobutene resins and methods for making said resins
 IN Foster, Pamela S., Midland, MI, United States
 Ecker, Ernest L., Midland, MI, United States
 Rutter, Jr., Edward W., Midland, MI, United States
 Moyer, Eric S., Midland, MI, United States
 PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
 PI US 5854302 19981229
 AI US 1994-224203 19940414 (8)
 RLI Continuation-in-part of Ser. No. US 1993-54999, filed on 29 Apr 1993, now abandoned
 DT Utility
 LN.CNT 1506
 INCL INCLM: 522/172.000
 INCLS: 526/281.000; 528/032.000; 556/453.000
 NCL NCLM: 522/172.000
 NCLS: 526/281.000; 528/032.000; 556/453.000
 IC [6]
 ICM: C08F002-46
 ICS: C08F010-08; C08G077-20
 EXF 522/172; 526/281; 528/32; 556/453; 428/391
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 5 OF 8 USPATFULL
 AN 97:96488 USPATFULL
 TI Flame-resistant heating body and method for making same
 IN Niibe, Akitoshi, Kamisu 3-7 29, Kamisu-cho, Kashima-gun, Ibaragi-ken, Japan
 Nakagawa, Kinichi, 1532 Koike-cho, Hamamatsu-City, Shizuoka-Pref, Japan
 PI US 5679277 19971021
 AI US 1995-398962 19950302 (8)
 DT Utility
 LN.CNT 593
 INCL INCLM: 219/543.000
 INCLS: 219/545.000; 219/482.000; 252/601.000
 NCL NCLM: 219/543.000
 NCLS: 219/482.000; 219/545.000; 252/601.000
 IC [6]
 ICM: H05B003-16
 ICS: H05B003-34; C09K021-00; B23K013-08
 EXF 219/211; 219/212; 219/213; 219/527; 219/528; 219/529; 219/543; 219/545; 219/501; 219/482; 219/497; 252/601; 252/608; 252/609; 252/500; 252/502
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 6 OF 8 USPATFULL
 AN 96:116457 USPATFULL
 TI Oligomerized cyclobutarene resins
 IN Oaks, Frank L., San Carlos, CA, United States
 Moyer, Eric S., Midland, MI, United States
 Rutter, Jr., Edward W., Midland, MI, United States
 Harris, Robert F., Midland, MI, United States
 PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
 PI US 5585450 19961217
 AI US 1995-465666 19950605 (8)
 RLI Division of Ser. No. US 1994-290197, filed on 15 Aug 1994 which is a continuation-in-part of Ser. No. US 1991-805395, filed on 10 Dec 1991, now abandoned
 DT Utility
 LN.CNT 2009
 INCL INCLM: 526/279.000

INCLS: 526/284.000
NCL NCLM: 526/279.000
NCLS: 526/284.000
IC [6]
ICM: C08F130-08
EXF 526/279; 526/284
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 7 OF 8 USPATFULL
AN 96:80092 USPATFULL
TI **Polybenzazole** fibers having improved tensile strength retention
IN So, Ying H., Midland, MI, United States
Martin, Steven J., Midland, MI, United States
Chau, Chieh-Chun, Midland, MI, United States
Wessling, Ritchie A., Midland, MI, United States
Sen, Ashish, Midland, MI, United States
Kato, Katsuhiko, Ikeda, Japan
Roitman, Daniel B., Menlo Park, CA, United States
Rochefort, Willie E., Corvallis, OR, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5552221 19960903
AI US 1994-366346 19941229 (8)
DT Utility
LN.CNT 938
INCL INCLM: 428/373.000
INCLS: 528/322.000; 528/327.000; 528/331.000; 528/340.000
NCL NCLM: 428/373.000
NCLS: 264/078.000; 264/129.000; 264/211.140; 264/211.150; 528/322.000;
528/327.000; 528/331.000; 528/340.000
IC [6]
ICM: B32B005-02
ICS: C08G073-22
EXF 528/183; 528/322; 528/327; 528/331; 528/337; 528/340; 528/342; 428/373;
264/331R
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L4 ANSWER 8 OF 8 USPATFULL
AN 95:36005 USPATFULL
TI Membranes having improved selectivity and recovery, and process for making same
IN Jensvold, John A., Benicia, CA, United States
Chary, Srikanth R., Fremont, CA, United States
Jacks, Wendy S., Indianapolis, IN, United States
Keller, Hans R., Concord, CA, United States
Parker, Theodore L., Alpharetta, GA, United States
Reddy, Damoder, Walnut Creek, CA, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5409524 19950425
AI US 1993-119800 19930910 (8)
RLI Continuation-in-part of Ser. No. US 1992-989159, filed on 1 Dec 1992, now abandoned
DT Utility
LN.CNT 678
INCL INCLM: 096/008.000
INCLS: 095/045.000; 096/013.000; 096/014.000; 055/DIG.005
NCL NCLM: 096/008.000
NCLS: 055/DIG.005; 095/045.000; 096/013.000; 096/014.000
IC [6]
ICM: B01D053-22
EXF 095/45; 095/47; 095/49; 095/51; 095/54; 096/4; 096/7-14; 055/524;
055/528; 055/DIG.5
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> s polybenzazole# and (aromatic amine# or phenol?)

113 POLYBENZAZOLE#
207726 AROMATIC
203783 AMINE#
15044 AROMATIC AMINE#
(AROMATIC(W)AMINE#)
162620 PHENOL?
L5 35 POLYBENZAZOLE# AND (AROMATIC AMINE# OR PHENOL?)

=> s polybenzazole# and aromatic amine# and phenol?

113 POLYBENZAZOLE#
207726 AROMATIC
203783 AMINE#
15044 AROMATIC AMINE#
(AROMATIC(W)AMINE#)
162620 PHENOL?
L6 1 POLYBENZAZOLE# AND AROMATIC AMINE# AND PHENOL?

=> d

L6 ANSWER 1 OF 1 USPATFULL
AN 92:80888 USPATFULL
TI Copolymers containing polybenzoxazole, polybenzothiazole and
polybenzimidazole moieties
IN Harris, William J., Midland, MI, United States
Hwang, Wen-Fang, Midland, MI, United States
PA The Dow Chemical Company, Midland, MI, United States (U.S. corporation)
PI US 5151489 19920929
AI US 1989-407973 19890915 (7)
RLI Continuation-in-part of Ser. No. US 1989-378360, filed on 7 Jul 1989
which is a continuation of Ser. No. US 1989-327925, filed on 23 Mar
1989, now patented, Pat. No. US 5030706 which is a continuation-in-part
of Ser. No. US 1988-256338, filed on 12 Oct 1988, now patented, Pat.
No. US 5089568
DT Utility
LN.CNT 4017
INCL INCLM: 528/183.000
INCLS: 528/128.000; 525/410.000; 525/411.000; 525/413.000; 525/415.000;
525/424.000; 525/425.000; 525/434.000
NCL NCLM: 528/183.000
NCLS: 525/410.000; 525/411.000; 525/413.000; 525/415.000; 525/424.000;
525/425.000; 525/434.000; 528/128.000
IC [5]
ICM: C08G075-32
EXF 528/128; 528/183; 525/410; 525/411; 525/413; 525/415; 525/424; 525/425;
525/434
CAS INDEXING IS AVAILABLE FOR THIS PATENT.